

#3  
Jormal  
Dawson  
2/18/99

1        **IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**  
2        **PRIORITY** PATENT APPLICATION SERIAL NO. .... 08/696,243  
3        **PRIORITY** FILING DATE ..... 08/13/96  
4        **INVENTORSHIP** ..... Schuegraf  
5        **PRIORITY** GROUP ART UNIT ..... 2813  
6        **PRIORITY** EXAMINER ..... M. Whipple  
7        **ATTORNEY'S DOCKET NO.** ..... MI22-1098  
8        **TITLE** ..... Semiconductor Processing Methods of Chemical Vapor Depositing  
9        SiO<sub>2</sub> on a Substrate

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11  
12        Assistant Commissioner for Patents  
13        Washington, D. C. 20231  
14        Attention: Official Draftsman  
15

16                                **SUBSTITUTE DRAWING REQUEST**

17                Please enter the enclosed substitute drawings in the  
18        above-referenced application in place of drawings originally filed. The  
19        content of the drawings are identical to those now on file in this  
20        application.  
21

1 Acknowledgment of receipt of the formal drawings and their  
2 acceptance into the file is requested.

Respectfully submitted,

Date:

12/15/98

By:

Lance R. Sadler

Reg. No.: 38,605

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Enclosures: 2 Formal Sheets of Drawings, Figs. 1-4